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ENVIRONMENTAL PROTECTION AGENCY

40 CFR Part 98

Mandatory Greenhouse Gas Reporting

CFR Correction

In Title 40 of the Code of Federal Regulations, Parts 96 to 99, revised as of July 1, 2014, on pages 696 through 698, in subpart I of part 98, tables I-5 through I-7 are corrected to read as follows:

TABLE I-5 TO SUBPART I OF PART 98—DEFAULT EMISSION FACTORS (1-U_{ij}) FOR GAS UTILIZATION RATES (U_{ij}) AND BY-PRODUCT FORMATION RATES (B_{ijk}) FOR MEMS MANUFACTURING

Process type factors	Process gas i											
	CF ₄	C ₂ F ₆	CHF ₃	CH ₂ F ₂	C ₃ F ₈	C-C ₄ F ₈	NF ₃ Remote	NF ₃	SF ₆	C ₄ F _{6a}	C ₃ F _{8a}	C ₄ F ₈ O _{2a}
Etch 1-U _i	0.7	10.4	10.4	10.06	NA	10.2	NA	0.2	0.2	0.1	0.2	NA
Etch BCF ₄	NA	10.4	10.07	10.08	NA	0.2	NA	NA	NA	10.3	0.2	NA
Etch BC ₂ F ₆	NA	NA	NA	NA	NA	0.2	NA	NA	NA	10.2	0.2	NA
CVD Chamber Cleaning 1-U _i	0.9	0.6	NA	NA	0.4	0.1	0.02	0.2	NA	NA	0.1	0.1
CVD Chamber Cleaning BCF ₄	NA	0.1	NA	NA	0.1	0.1	20.02	20.1	NA	NA	0.1	0.1
CVD Chamber Cleaning BC ₃ F ₈	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	0.4

Notes: NA = Not applicable; i.e., there are no applicable default emission factor measurements for this gas. This does not necessarily imply that a particular gas is not used in or emitted from a particular process sub-type or process type.

¹ Estimate includes multi-gas etch processes.

² Estimate reflects presence of low-k, carbide and multi-gas etch processes that may contain a C-containing fluorinated GHG additive.

TABLE I-6 TO SUBPART I OF PART 98—DEFAULT EMISSION FACTORS (1-U_{ij}) FOR GAS UTILIZATION RATES (U_{ij}) AND BY-PRODUCT FORMATION RATES (B_{ijk}) FOR LCD MANUFACTURING

Process type factors	Process Gas i								
	CF ₄	C ₂ F ₆	CHF ₃	CH ₂ F ₂	C ₃ F ₈	C-C ₄ F ₈	NF ₃ Remote	NF ₃	SF ₆
Etch 1-U _i	0.6	NA	0.2	NA	NA	0.1	NA	NA	0.3
Etch BCF ₄	NA	NA	0.07	NA	NA	0.009	NA	NA	NA
Etch BCF ₃	NA	NA	NA	NA	NA	0.02	NA	NA	NA
Etch BC ₂ F ₆	NA	NA	0.05	NA	NA	NA	NA	NA	NA
CVD Chamber Cleaning 1-U _i	NA	NA	NA	NA	NA	NA	0.03	0.3	0.9

Notes: NA = Not applicable; i.e., there are no applicable default emission factor measurements for this gas. This does not necessarily imply that a particular gas is not used in or emitted from a particular process sub-type or process type.

TABLE I-7 TO SUBPART I OF PART 98—DEFAULT EMISSION FACTORS (1-U_{ij}) FOR GAS UTILIZATION RATES (U_{ij}) AND BY-PRODUCT FORMATION RATES (B_{ijk}) FOR PV MANUFACTURING

Process type factors	Process Gas i								
	CF ₄	C ₂ F ₆	CHF ₃	CH ₂ F ₂	C ₃ F ₈	C-C ₄ F ₈	NF ₃ Remote	NF ₃	SF ₆
Etch 1-U _i	0.7	0.4	0.4	NA	NA	0.2	NA	NA	0.4
Etch BCF ₄	NA	0.2	NA	NA	NA	0.1	NA	NA	NA
Etch BC ₂ F ₆	NA	NA	NA	NA	NA	0.1	NA	NA	NA
CVD Chamber Cleaning 1-U _i	NA	0.6	NA	NA	0.1	0.1	NA	0.3	0.4
CVD Chamber Cleaning BCF ₄	NA	0.2	NA	NA	0.2	0.1	NA	NA	NA

Notes: NA = Not applicable; i.e., there are no applicable default emission factor measurements for this gas. This does not necessarily imply that a particular gas is not used in or emitted from a particular process sub-type or process type.

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